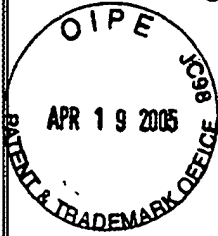


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APPLICANT
SHANMUGASUNDRAM et al.

FILING DATE
August 31, 2001

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2823

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

January 24, 2005. International Preliminary Examination Report from PCT Application No. PCT/US02/19117

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